Amendments to the claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method for manufacturing a metal master comprising the steps of:

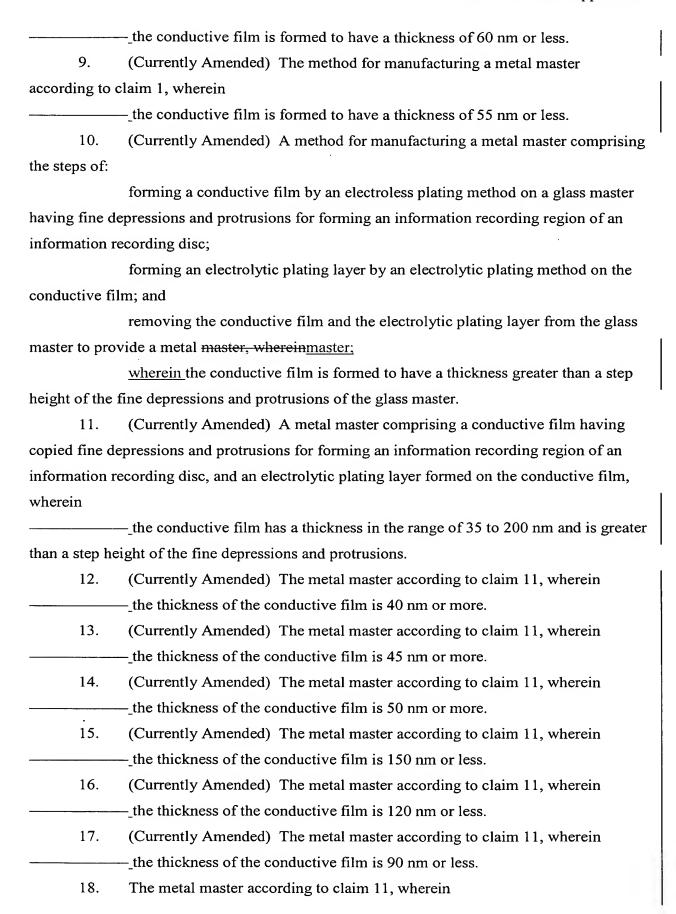
forming a conductive film by an electroless plating method on a glass master having fine depressions and protrusions for forming an information recording region of an information recording disc;

forming an electrolytic plating layer by an electrolytic plating method on the conductive film; and

removing the conductive film and the electrolytic plating layer from the glass master to provide a metal master, whereinmaster:

wherein the conductive film is formed to have a thickness of 35 to 200 nm.

- 2. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein
- _____the conductive film is formed to have a thickness of 40 nm or more.
- 3. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein
- _____the conductive film is formed to have a thickness of 45 nm or more.
- 4. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein
- _____the conductive film is formed to have a thickness of 50 nm or more.
- 5. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein
- _____the conductive film is formed to have a thickness of 150 nm or less.
- 6. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein
- _____the conductive film is formed to have a thickness of 120 nm or less.
- 7. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein
- _____the conductive film is formed to have a thickness of 90 nm or less.
- 8. (Currently Amended) The method for manufacturing a metal master according to claim 1, wherein



	-the thickness of the conductive film is 60 nm or less.
19.	(Currently Amended) The metal master according to claim 11, wherein
	-the thickness of the conductive film is 55 nm or less.